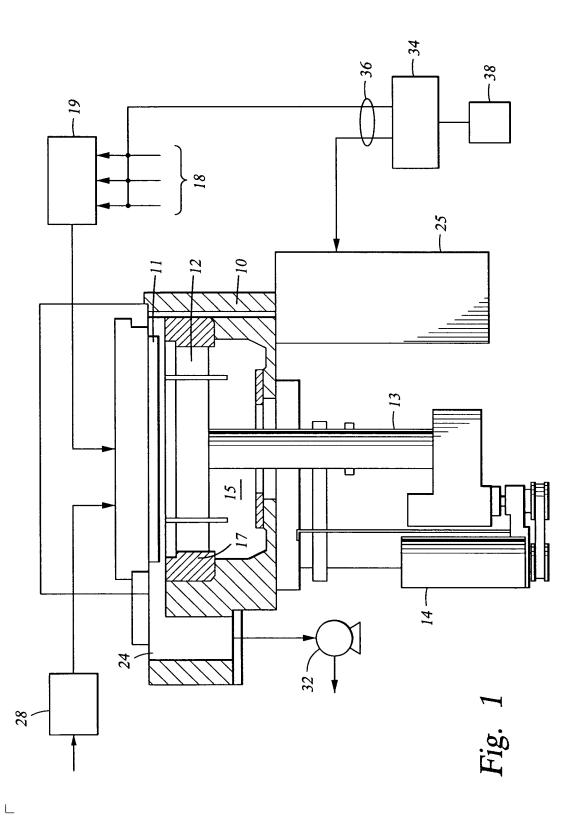


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U.S. SERIAL NO.: 10/718,887 FILED: NOVEMBER 21, 2003
APPLICANT: APPLIED MATERIALS, INC.
TITLE: A METHOD OF ELIMINATING PHOTORESIST POISONING IN DAMASCENE APPLICATIONS
INVENTORS: PING XU, ET AL.

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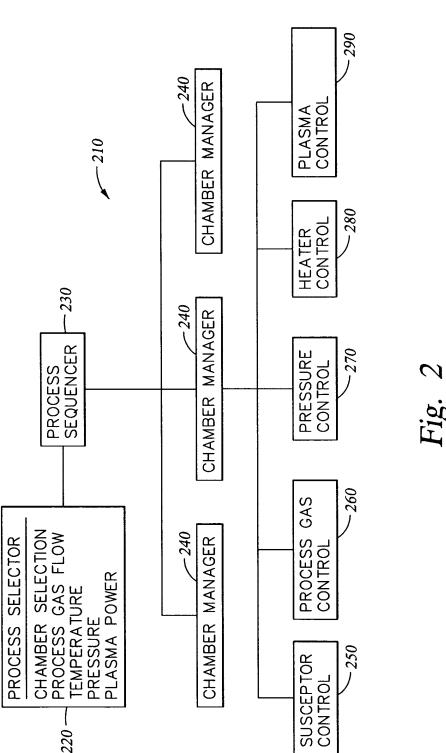
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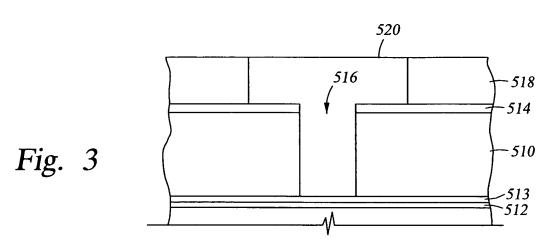


Fig. 4A

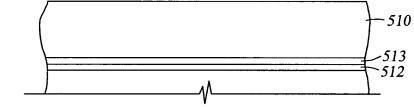


Fig. 4B

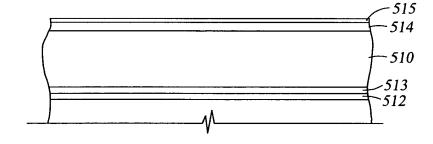
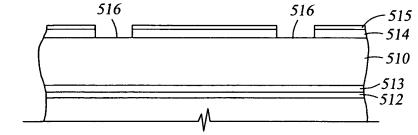


Fig. 4C

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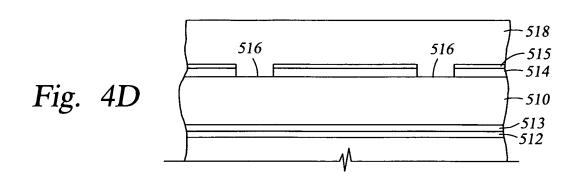
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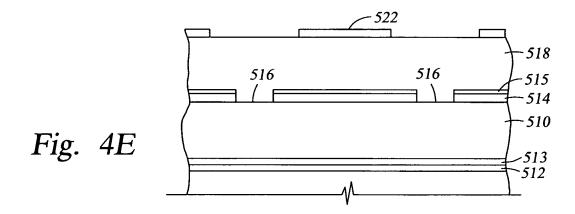
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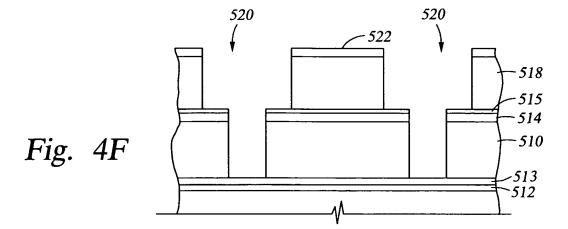
PING XU, ET AL. INVENTORS:

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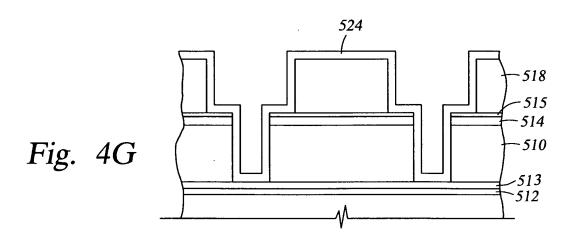
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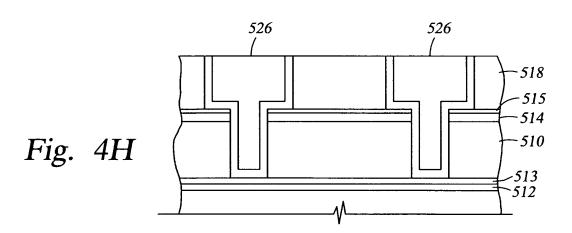
DAMASCENE APPLICATIONS

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